High Purity
SPUTTERING
TARGET

ITO

NANOSHEL
Creating Miracles in Black

INDIUM TIN Oxide
Sputtering Target

Indium tin oxide sputtering target thin films have wide utility because they are electrically conductive and transparent at visible wavelengths, so it is used for coating purpose. A preferred method for making highest quality ITO coatings is reactive sputtering from targets of mixed indium and tin oxides.

Quick Facts

Product	:	Indium Tin Oxide Sputtering Target
Stock No	:	NS6130-10-1209
CAS	:	50926-11-9

Application

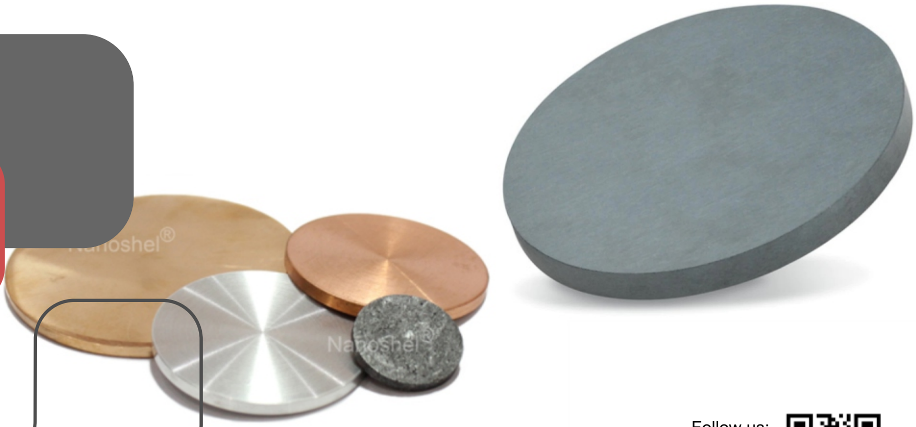
- ✓ TN/STN LCD
- ✓ CF TFT
- ✓ OLED
- ✓ Touch Panel
- ✓ Solar Cell
- ✓ Low-e, AR/AS
- ✓ Indium Tin Oxide (ITO) high density sputtering target

Additional Characteristics

Stock No.	Purity	Diameter	Thickness
NS6130-10-1209	99.99%	50.8 mm ± 1mm	3 mm ± 0.5mm

Technical Specification

Molecular Formula	Molecular Weight	Melting Point
ITO	428.34g/mol	1800°C



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